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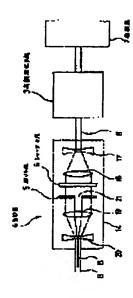
ISHIYAMA NORITAKA

(54) YAG LASER BEAM MACHINE FOR PRECISELY MACHINING THIN FILM

(57)Abstract:

PURPOSE: To provide a YAG laser beam machine capable of machining thin films with such a precision as required for drawing patterns onto photomasks used in e.g. a process for manufacturing printed boards or process for manufacturing semiconductors.

CONSTITUTION: Being isolated from the outside part of laser beams B, an aperture means 5 for thinning a beam diameter is provided, a shutter means 6 for ON-OFF controlling the irradiation of the laser beams is also provided in the outside of an oscillator 2, and further a higher harmonizing means 3 for forming the laser beams into higher harmonics is provided.



LEGAL STATUS

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